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(12) **United States Design Patent** (10) **Patent No.: US D446,506 S**
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(54) **MONOLITH PROCESSING SYSTEM PLATFORM**

(75) Inventor: **Avi Tepman**, Cupertino, CA (US)

(73) Assignee: **Applied Materials, Inc.**, Santa Clara, CA (US)

(**) Term: **14 Years**

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(51) **LOC (7) Cl.** **13-03**
(52) **U.S. Cl.** **D13/182**
(58) **Field of Search** D13/182, 199

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Primary Examiner—Brian N. Vinson
(74) *Attorney, Agent, or Firm*—Thomason, Moser & Patterson, L.L.P.

(57) **CLAIM**

The ornamental design for a monolith processing system platform.

DESCRIPTION

FIG. **1** is a top perspective view of a monolith processing system platform of the present invention;

FIG. **2** is a perspective view showing substantially the top of a monolith processing system platform of the present invention;

FIG. **3** is a perspective view showing substantially one side of a monolith processing system platform of the present invention;

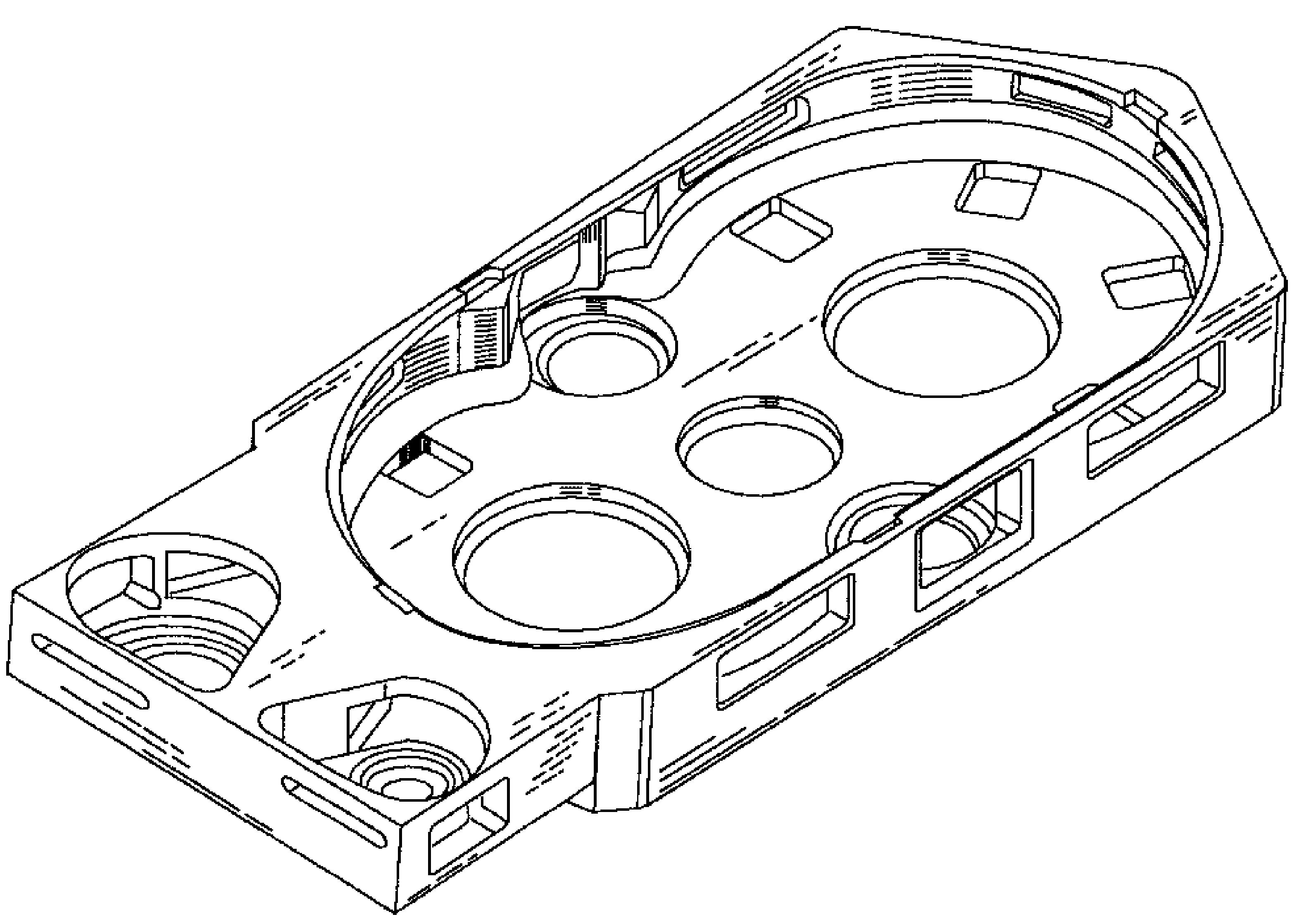
FIG. **4** is a perspective view showing substantially another side of a monolith processing system platform of the present invention;

FIG. **5** is a perspective view showing substantially the back end of a monolith processing system platform of the present invention; and

FIG. **6** is a perspective view showing substantially the front end of a monolith processing system platform of the present invention; and,

FIG. **7** is a perspective view showing substantially the bottom of a monolith processing system platform of the present invention.

1 Claim, 5 Drawing Sheets



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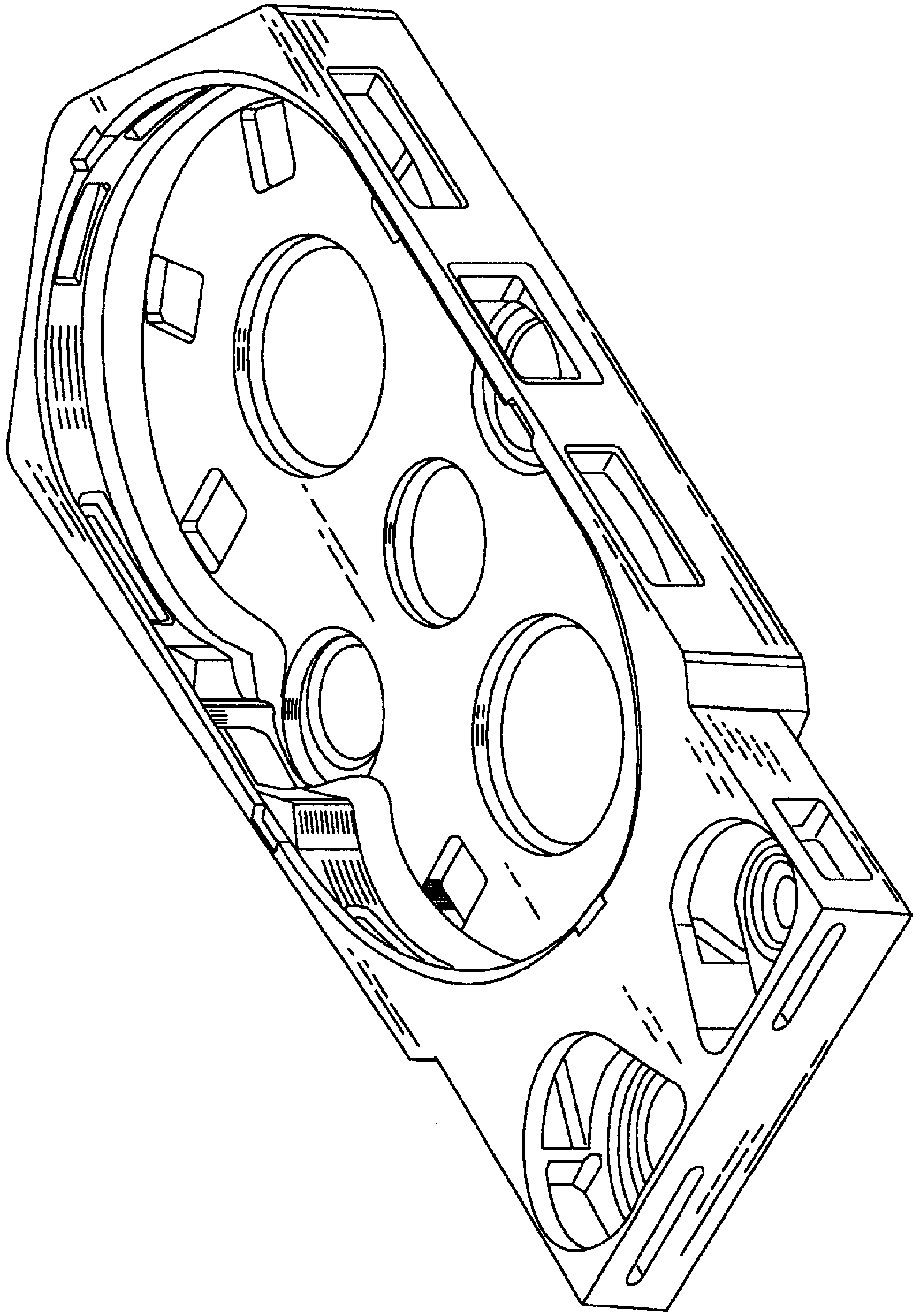
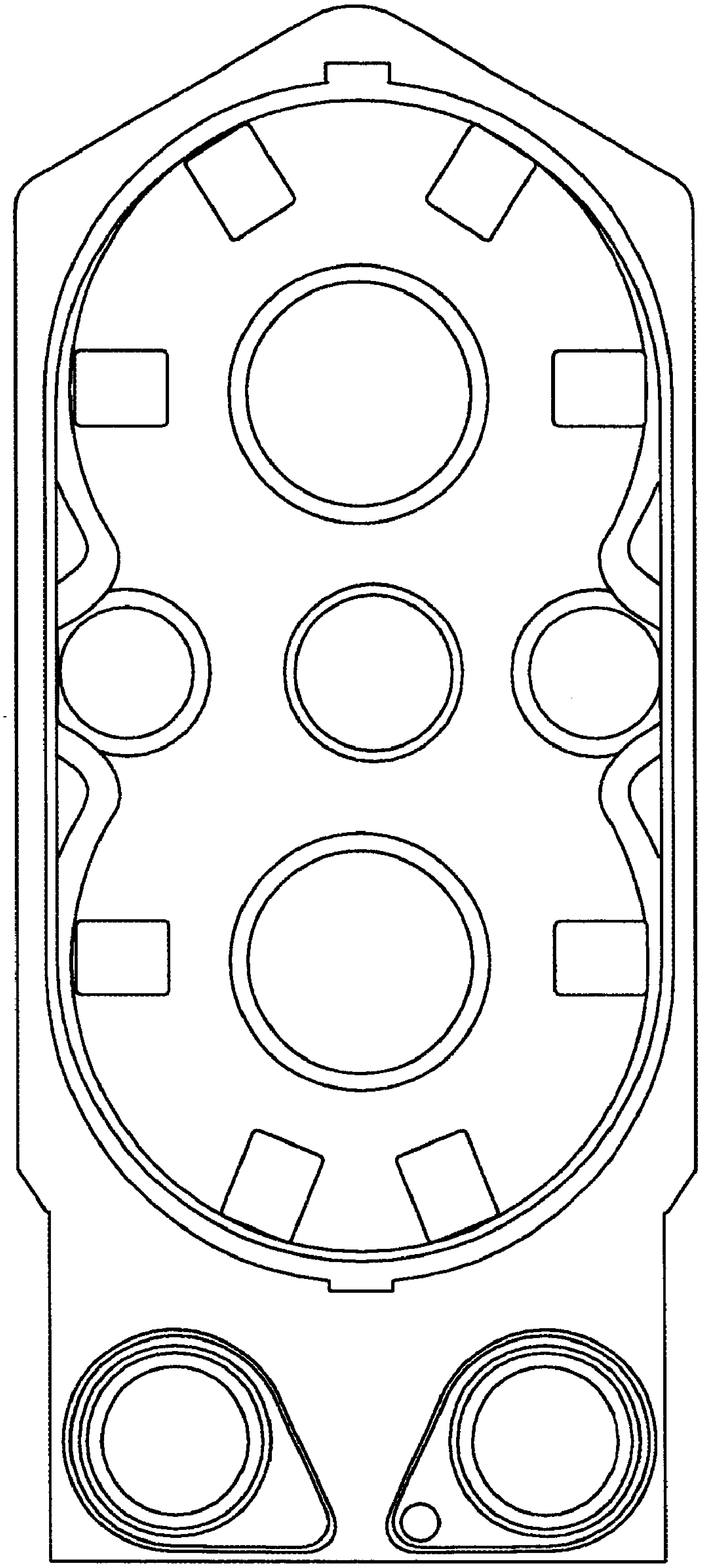


Fig. 1

Fig. 2



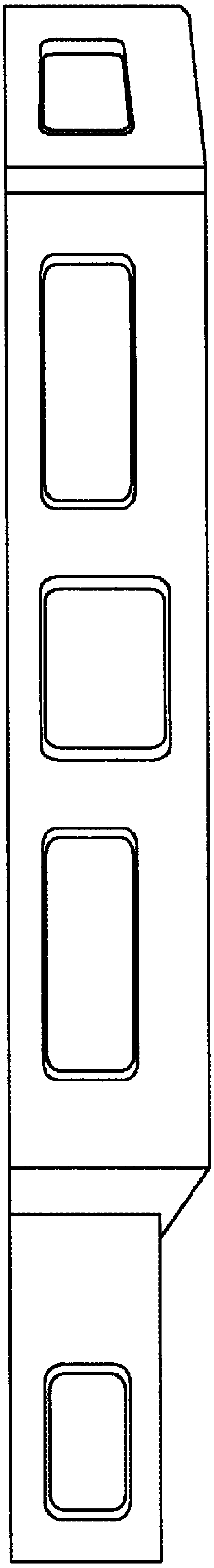


Fig. 3

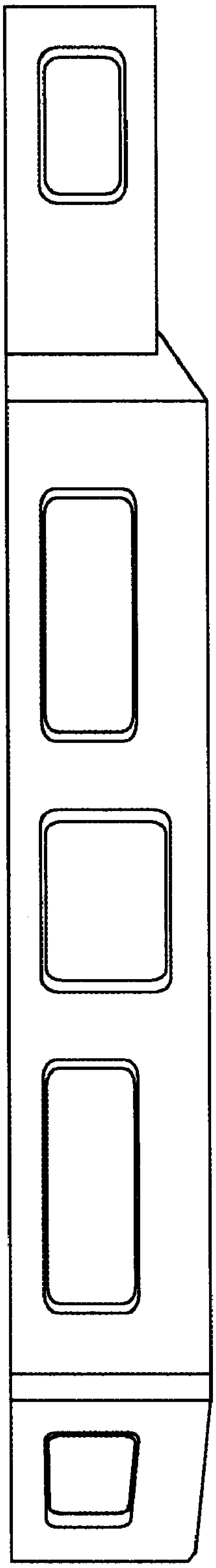


Fig. 4

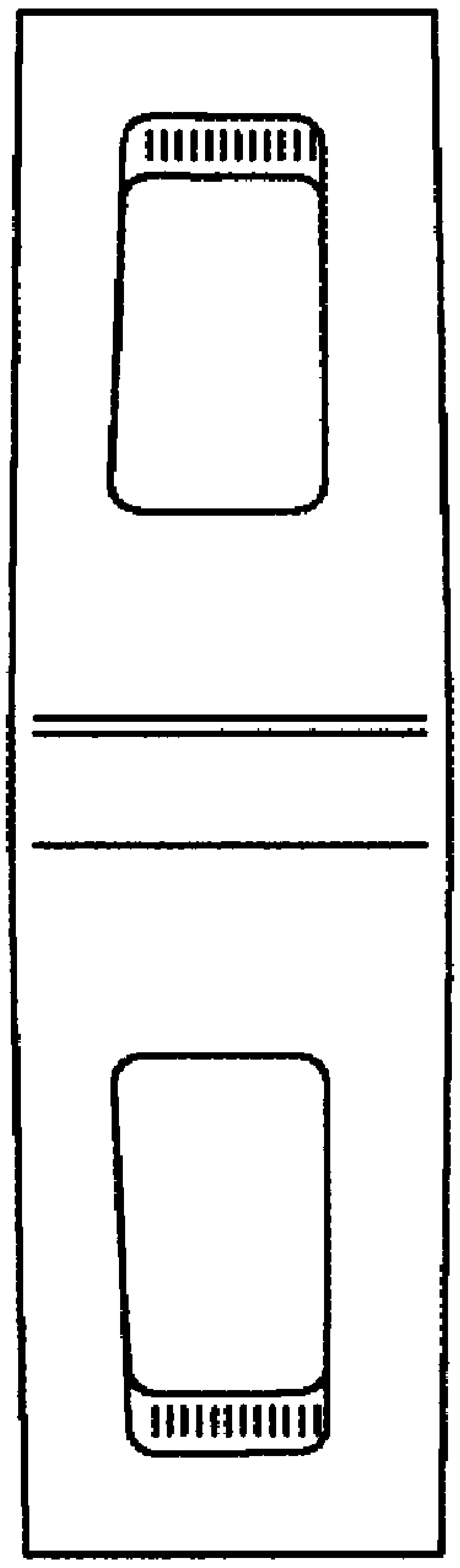


Fig. 5

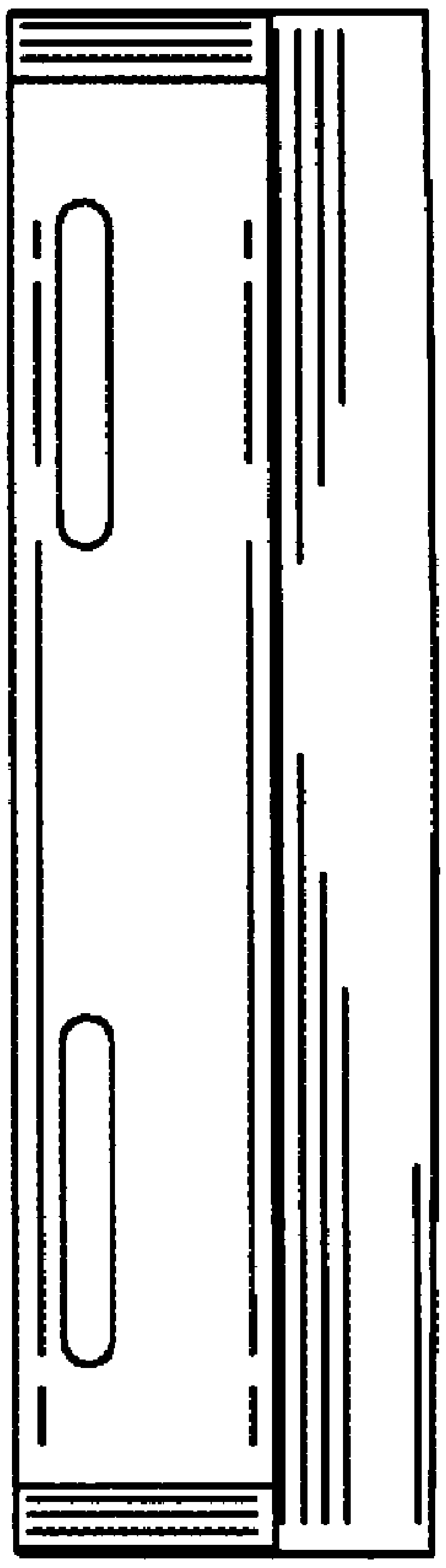


Fig. 6

Fig. 7